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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : Box AF
Satoshi Watanabe et al. :
Serial No.: 09/401,490 : Group Art Unit: 1765
Filed: September 22, 1999 : Examiner: V. Perez-Ramos

For: RESIST COMPOSITION AND PATTERNING METHOD

AMENDMENT UNDER 37 CFR §1.116

Assistant Commissioner of Patents
Washington, DC 20231

Sir:

In response to the Office Action mailed November 21, 2002, please amend the above-application as follows and consider the remarks.

IN THE CLAIMS

Please cancel claim 5 without prejudice or disclaimer.

Please amend the following claims:

B₁ 1. (Amended) A resist composition comprising a base polymer and a fluorochemical surfactant which functions to reduce the contact angle at the interface between the surface of the resist composition coated onto a substrate and water or an aqueous base developer as the amount of the fluorochemical surfactant increases.

132 19. (Amended) The resist composition of claim 1 wherein the base polymer is polyhydroxystyrene, poly[(t-butyl acrylate)-(hydroxystyrene)] copolymer, poly[(t-butyl methacrylate)-(methyl methacrylate)-(polymethacrylic acid)] copolymer, or poly[(t-butyl-5-norbornene-2-carboxylate)-(maleic anhydride)-(5-norbornene-2,3-dicarboxylic anhydride)] copolymer.